



Unusually selective synthesis of chlorohydrooligosilanes†

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New pathways towards molecular chlorohydrooligosilanes enable their one-pot synthesis in preparative amounts either by the selective chlorination of the corresponding perhydrosilanes with HCl/AlCl₃ or by the partial hydrogenation of perchlorooligosilanes with substoichiometric amounts of iBu₂AlH. The unexpected selective formation of Cl₃Si-substituted species in the partial hydrogenation reactions could be related to mechanistic aspects.

Chlorosilanes, especially chlorohydrosilanes, are ideal precursors for the generation of hyperpure polycrystalline silicon. Because of the dramatic rise of photovoltaic applications, the production capacity of polysilicon reached 600 kton per year at the end of 2018.¹ The vast majority of polycrystalline Si produced worldwide is made by the chemical vapor deposition of HSiCl₃.² Less than 10% of all solar grade silicon is currently manufactured from silicon hydrides such as SiH₄ in spite of their lower decomposition temperatures and the resulting lower energy cost incurred during the deposition process. The major drawbacks of silicon hydrides are their high production costs and difficulty in handling because of their pyrophoric nature. Therefore, the search for alternative precursor materials for silicon deposition is still an issue of primary importance.³

Based on calculations, two mechanisms for the deposition of silicon from HSiCl₃ are possible. The disilane mechanism proposed by Swihart and Carr *et al.*⁴ and the radical mechanism by Cavallotti *et al.*⁵ In both mechanisms, the formation of disilanes as reaction intermediates plays a crucial role by enhancing the gas phase reactivity. This is due to their increased reactivity, determined by the relatively low Si–Si bond energy and small barriers for Cl and H intramolecular transfers. Therefore, it can be anticipated that chlorohydrooligosilanes will outperform the state-of-the-art precursors concerning their

film deposition properties. A recently published study actually showed the formation of higher quality films at higher deposition rates using atomic layer deposition (ALD) processes for the precursor molecule HSi₂Cl₅ as compared to Si₂Cl₆.⁶

However, the state-of-the-art synthetic protocols of chlorohydrooligosilanes are not straightforward. Partial halogenation reactions of di-, tri- and tetrasilane with BX₃, HX/AlX₃, AgX, SnX₄, HgX₂ or X₂ (X = Cl, Br, I) afforded product mixtures which could only be analyzed after further derivatization of the initial products.⁷ The partial hydrogenation of perchlorooligosilanes by treatment with substoichiometric amounts of LiAlH₄ or Bu₃SnH was also found to be rather unselective.^{8,9} Additionally, selected halohydrooligosilanes were prepared by the halodephenylation of appropriately substituted phenylated precursors with anhydrous HX.¹⁰ The challenge of this method is the preparation of the starting materials which frequently involves tedious multi-step procedures. In a more recent study, we observed the clean formation of 1,2,3,4-tetrachloroneopentasilane **2** after treatment of neopentasilane **1** with 3.5 equivalents of SnCl₄.¹¹ To the best of our knowledge this was the first example of a direct and selective functionalization of a higher silicon hydride on a preparative scale.

A major disadvantage of SnCl₄ as a halogenating reagent is the formation of huge amounts of SnCl₂, which are difficult to remove completely, particularly on a larger scale. Thus, we investigated the chlorination of neopentasilane with gaseous HCl in the presence of AlCl₃ as the catalyst. When dry HCl gas was bubbled through a benzene solution of neopentasilane containing catalytic amounts of AlCl₃ at 70 °C for 15 minutes, compound **2** was obtained with remarkable selectivity along with 1,2,3-trichloroneopentasilane **3** as the by-product (Scheme 1). Removal of the solvent and the catalyst and recondensation of the crude product afforded a mixture of **2** (85%) and **3** (15%) in >60% yield. Attempts to separate both components using distillation or crystallization were unsuccessful.

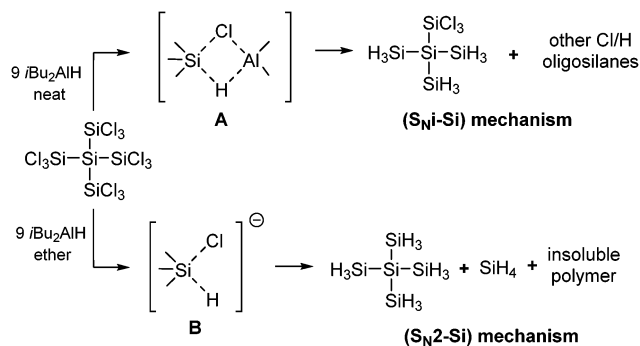
An even more appealing approach to chlorohydrooligosilanes is the partial hydrogenation of perchlorooligosilanes with substoichiometric amounts of iBu₂AlH. This pathway enables the

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Scheme 3 Mechanism of partial hydrogenation of 7.

DFT calculations at the SMD (pentane) M06-2X-D3/aug-cc-pVTZ level of theory were performed on the reaction of $\text{Cl}_3\text{Si-SiCl}_3$, $\text{H}_3\text{SiSiCl}_3$, $\text{H}_3\text{SiSiHCl}_2$, and $\text{H}_2\text{SiSiH}_2\text{Cl}$ with HALMe_2 . For $\text{Cl}_3\text{SiSiCl}_3$ which is the best suited test system, we were not able to locate all structures (ground states and transition states) on the energy surface. For $\text{H}_3\text{SiSiCl}_3$, $\text{H}_3\text{SiSiHCl}_2$, and $\text{H}_2\text{SiSiH}_2\text{Cl}$ the reaction path *via* intermediate/transition state A did not show any selectivity in terms of calculated activation energies ((1) reduction step: $\Delta\Delta G_{\text{AE}}^0 = 8.6 \text{ kcal mol}^{-1}$; (2) reduction step: $\Delta\Delta G_{\text{AE}}^0 = 9.6 \text{ kcal mol}^{-1}$; (3) reduction step: $\Delta\Delta G_{\text{AE}}^0 = 11.6 \text{ kcal mol}^{-1}$). In contrast, the calculated activation energies would favor a slightly preferred reaction at the higher chlorinated Si atom, contradicting our experimental observations. Thus, we attribute the unexpected selectivity of our hydrogenation reactions in non-coordinating solvents more to a steric than to an electronic effect. We reasoned that due to the presence of the sterically demanding *i*Bu-groups in transition state A further substitution preferably occurs at the sterically less encumbered Si-center, which is the Si atom bearing already one or two hydrogens leaving the residual SiCl_3 groups rather untouched. This steric effect more or less outperforms the electronic influence of the Cl substituents mentioned above leading to the predominant formation of products 4–7 containing exclusively $\text{Cl}_3\text{Si-}$ and $\text{H}_3\text{Si-}$ moieties. Further support for this picture was gained from the observation that the reduction of 7 with iBu_2AlH in diethyl ether does not show any selectivity. When 7 was reacted with substoichiometric amounts of iBu_2AlH in diethyl ether solution only small amounts of neopentasilane 1 were formed along with insoluble polymeric material and SiH_4 . In this case the hydrogen atom in $\text{iBu}_2\text{AlH-Et}_2\text{O}$ containing formally tetravalent aluminum is far more hydridic and nucleophilic and the reaction proceeds *via* a $\text{S}_{\text{N}}2$ mechanism.^{16b} As a consequence the reduction is accompanied by Si–Si bond scission and redistribution reactions and occurs rather unselectively just as found for the hydrogenation of chlorosilanes with LiAlH_4 in diethyl ether.

In conclusion, we have introduced two new innovative strategies for the synthesis of chlorohydrooligosilanes in gram quantities. In particular, it has been discovered that substoichiometric amounts of neat iBu_2AlH react with perchloro-oligosilanes, resulting in the formation of products containing exclusively $\text{Cl}_3\text{Si-}$ and $\text{H}_3\text{Si-}$ moieties. Si–Si bond scission and oligomerization reactions do not occur at all which contrasts the behavior of the more common hydrogenation reagent

LiAlH_4 /diethyl ether described in the literature. Different reaction mechanisms ($\text{S}_{\text{N}}2\text{-Si}$ and $\text{S}_{\text{N}}\text{i-Si}$) operative in polar and unpolar environments could be made responsible for this unexpected discrepancy. The target molecules of this study are of particular importance for potential applications as alternative precursors for the deposition of hyperpure polycrystalline silicon. Corresponding experiments are currently underway in our laboratories.

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Conflicts of interest

There are no conflicts to declare.

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